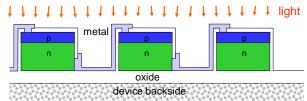


Proposing c-Si photo cells with 3D wiring



If 3D metal wiring is possible at the last step of fabrication, high-temp. oxide isolation film can be used. SiO₂ film realizes good isolation and voltage summing.

Wiring using vertical sidewall will be the best design for minimizing shadow area.

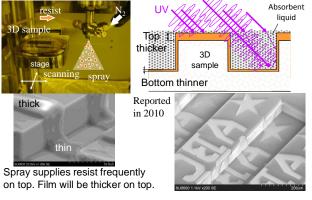
Vertical side walls are still challenging Angle sensor Slant side walls **T**UDelft Sarro, Tr.'11 IC probe card actuator w. Esashi w. Hane тоноки Induction coil, Xinxin Li, MEMS200 Vertical side walls Resist for Pattern size bottom width: 200µm corner gap : 300μm 🧷 coverage w. Oohira

Aim

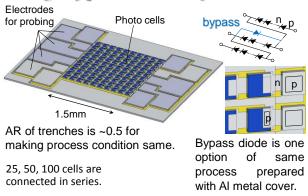
- Realizing micro-power source of c-Si photo cells connected in series with 3D wiring over vertical sidewall.
- ➤ Driving electrostatic micromirror using the realized micro-power source.

Processing for 3D wiring: resist spraying & absorbent liquid immersion angled exposure

w. Aoyagi



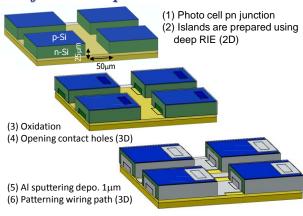
Design of photo cell array



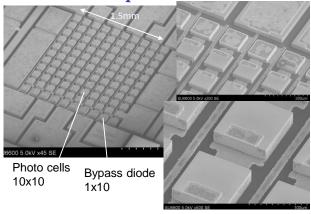
Design of individual photo cells

	_	
1	2	3
10x10	5x10	5x5
AI 100μm	E 00 € 250μm	receiving area
35x70		
75	90	96
	E ↑ AI ← ↑ 100μm	10x10 5x10 Entering Al 100µm 250µm 35x70

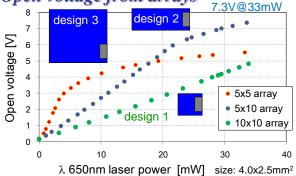
3D fabrication process



Fabricated 3D power source

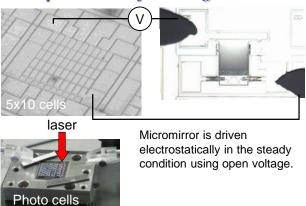


Open voltage from arrays

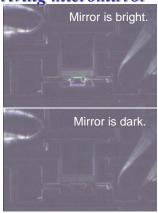


Larger effective area increases voltage with lower power. Number of cells is for increasing voltage after saturation.

Micro-power source for driving micromirror



Driving micromirror







 $V_{\it output}$ is set at 7.0V.

Conclusion

- ➤ Micro-power source based on crystalline Si photo cell islands is fabricated using thermally grown SiO₂ isolation film.
- ➤ 100, 50, and 25 cells are connected in series using 3D wiring over vertical side wall minimizing shadow area.
- ➤ Under red laser illumination, open voltage of 7.3V is confirmed from 50 cells.
- ➤ Electrostatic micromirror is driven applying the voltage obtained from micro-power source.